

HotAging — Impact of Power Dissipation on Hardware Degradation

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On chip power dissipation → increases temperature

(Almost) all aging mechanism depend also on temperature

HotAging - How does power dissipation impact circuit degradation over time (*aging*)?





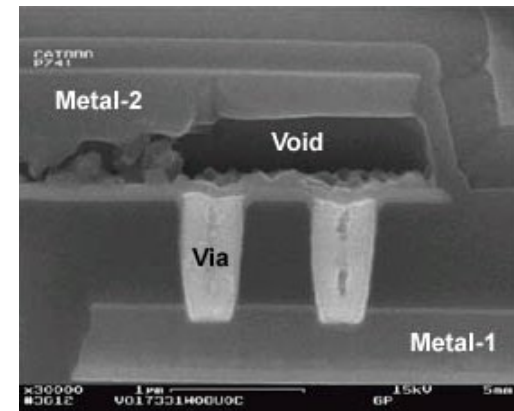
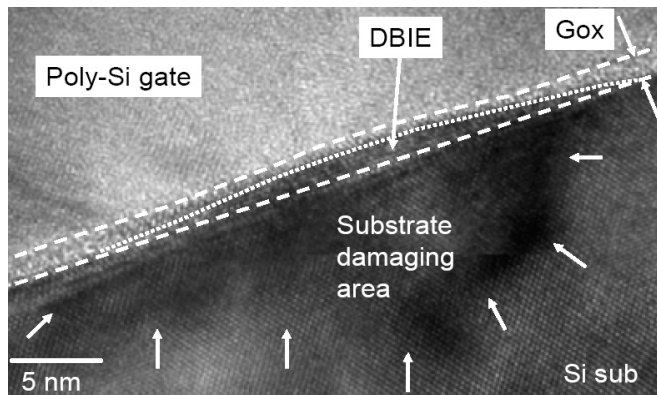
- Aging Mechanism
- Analysis Environment
- Results
- Conclusions



Aging

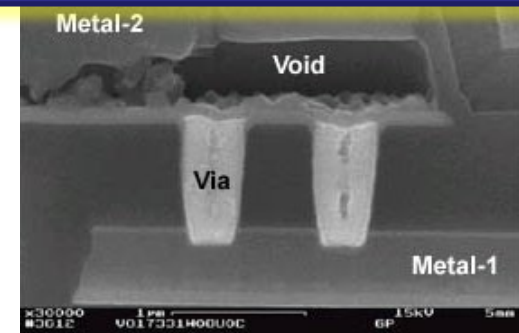
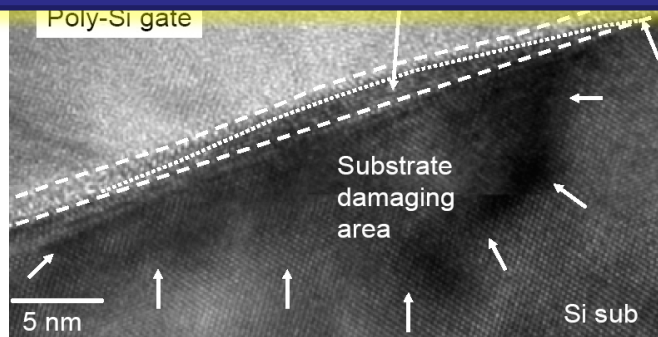


- Bias Temperature Instability (BTI)
 - Electric field over oxide leads to accumulation of 'traps' into silicon-oxide interface $\rightarrow v_{th}$ increase
- Time-Dependent Dielectric Breakdown (TDDB)
 - Tunneling current through gate oxide generates path from oxide to channel $\rightarrow v_{th}$ increase
- Electromigration
 - Transport of material caused by gradual movement of ions in wires $\rightarrow delay$ increase



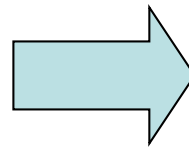
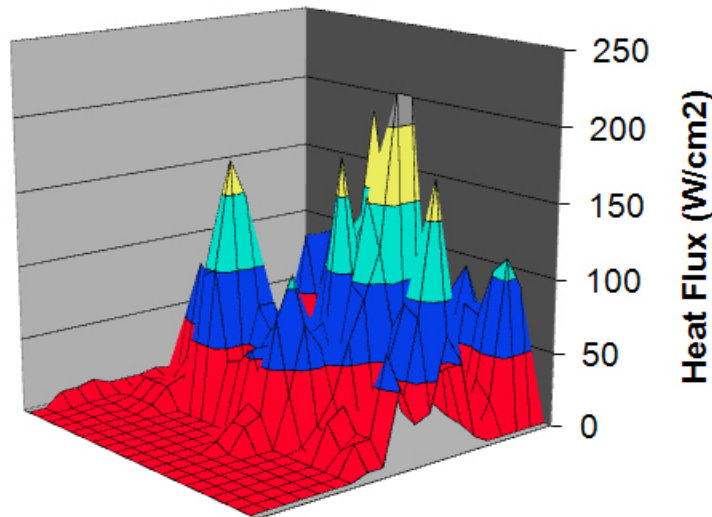
- Time-Dependent Dielectric Breakdown (TDDB)
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Acceleration due to higher Temperature

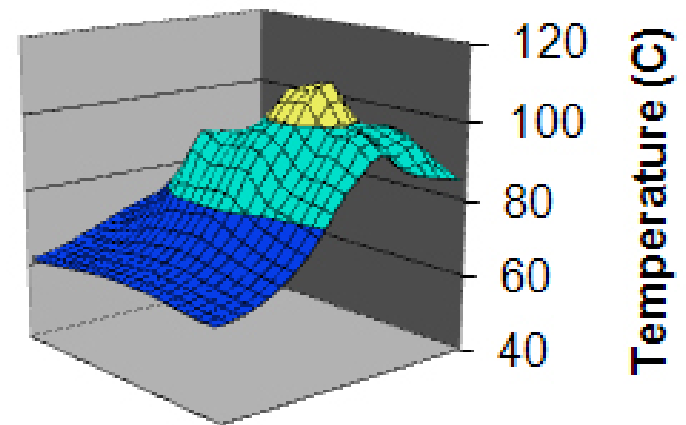


- Power dissipation can be directly related to temperature

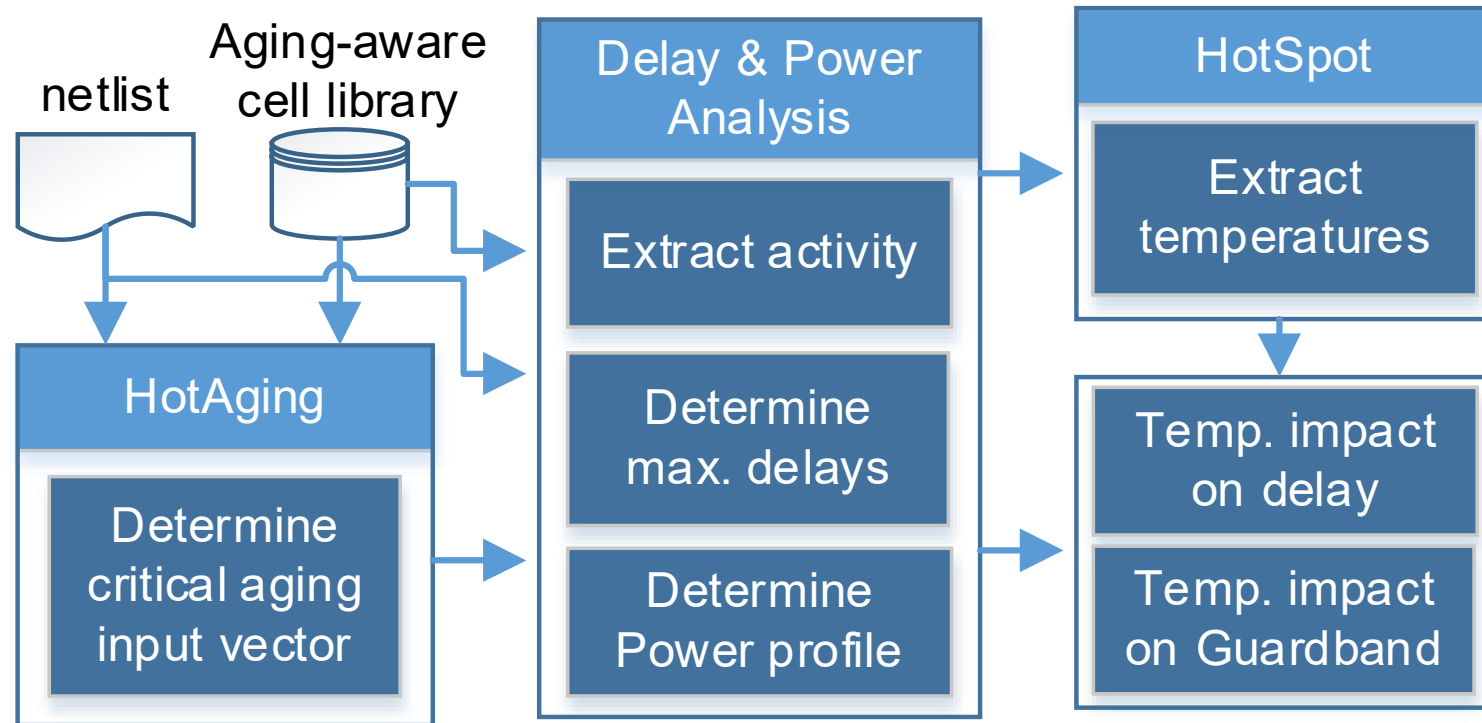
Power Map



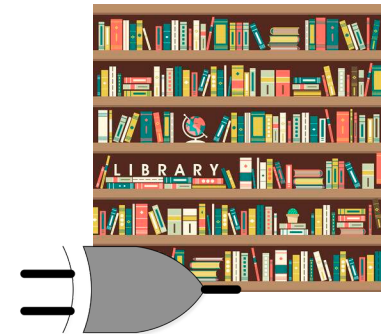
On-Die Temperature



- Principal analysis flow



- Aging analysis on **SPICE level**
 - Several models with **good prediction**
 - High flexibility in terms of aging parameters
 - Supported by EDA tools (e.g. Eldo, MOSRA, RelXpert)
 - **Inapplicable** for designs > 1000 devices
- Analysis on **cell level**
 - No support by industry
 - Lower flexibility in terms of aging parameters
 - Lower accuracy
 - **Applicable** for $>1M$ devices





- Principal flow
 - Based on (freely available) 45nm technology and cell library (FreePDK)
 - BTI aging simulated via its impact on threshold voltage V_{th} and mobility μ
 - Considered BTI factor: stress/recovery time via input duty-cycle
 - All parameters taken from literature
 - All cell characterized for with Cadence Liberate / SPECTRE
 - *Note: temperature impact considered in later step*



- Aging aware characterization
 - Duty-cycle (dc) varied in steps of 10% for all cell inputs
→ each cell with 11 (1 input) and 121 (2 inputs) versions for different combinations of input signal probabilities
 - 17 cells (comb/seq)
- Example:
 - INV1 with 40% dc: INV1_40
 - NAND2 with 1st input 20% dc and 2nd input 70% dc: NAND2_20_70



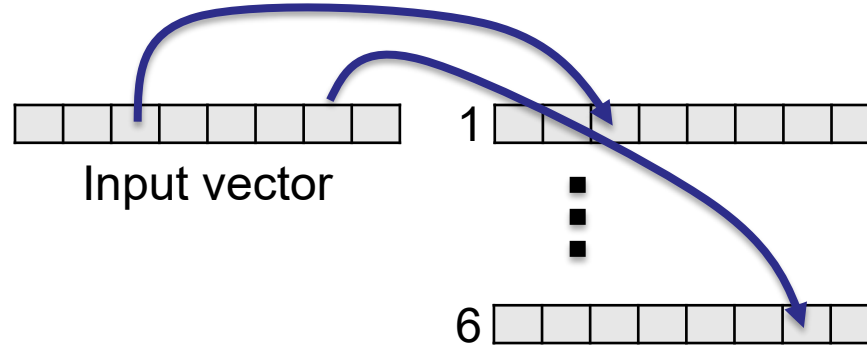
- Observations
 - Many aging mechanism are data-dependent
 - Power dissipation is data-dependent
- Question: What would be a critical combination of input vectors for maximum aging and power dissipation?
- Hot-Aging algorithm
 - Genetic algorithm
 - Two phases:
 1. Determination of critical aging input vector
 2. In the following: determination of critical power input vectors

Hot-Aging Algorithm

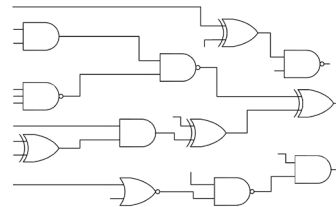


Phase 1

Invert bit (=mutation)



Apply to



Netlist

If new best

Fitness:

Nr. signals in critical paths @GND
(worst case for NBTI)

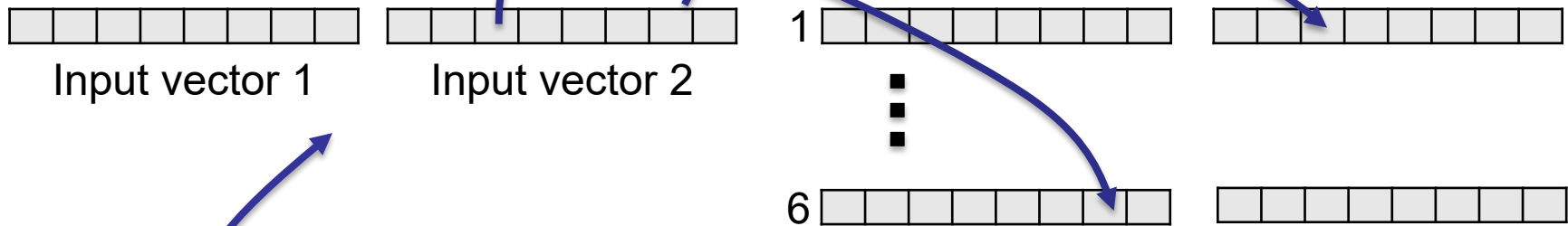


Hot-Aging Algorithm

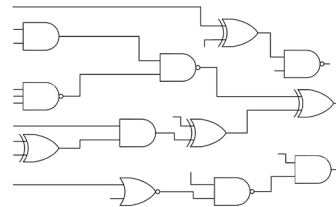


Phase 2

Invert bit (=mutation)



If new best



Netlist

Fitness:

Nr. signals in critical paths @GND +
Switched capacitance





- Extraction of power dissipation and max. delay via Modelsim and Synopsys DesignCompiler for determined input vectors using aging-aware cell library
- Extraction of temperature via HotSpot
- Temperature-dependent acceleration factor:

$$AF_{BTI}^{T_{op}, T_0} = \exp \left[\frac{E_{aBTI} \cdot (T_{op} - T_0)}{k_B \cdot T_{op} \cdot T_0} \right]$$

- With:
 - T_{op} – Actual temperature during operation
 - T_0 – Reference temperature (125°C)
 - E_{aBTI} – activation energy (0.58),
 - k_B – Boltzmann's constant



- Delay dependency (approx.) of v_{th} and μ :

$$t_d \propto \left[\mu^{-2} (V_{DD} - v_{th} - \Delta v_{th})^2 \right]^{-1}$$

- Delay increase due to BTI over period of 10 years

$$\Delta t_{d,T_{op}} = \frac{\Delta t_{d,T_0}}{\alpha \cdot t_{d,init}} \left(t_{10} \cdot AF_{BTI}^{T_{op},T_0} \cdot \beta \right)^\gamma$$

- With:
 - $\Delta t_{d,T_0}$ – Delay degradation if operated at T_0 for 10 years
 - $t_{d,init}$ – Pristine delay
 - t_{10} – 10 years
 - α, β, γ – Extracted parameters for chosen technology



- Guard-band (Δt_{guard}): extra delay added to clock against parameters variations (incl. due to aging)
- Extracted model for determining time until delay increase is beyond Δt_{guard}

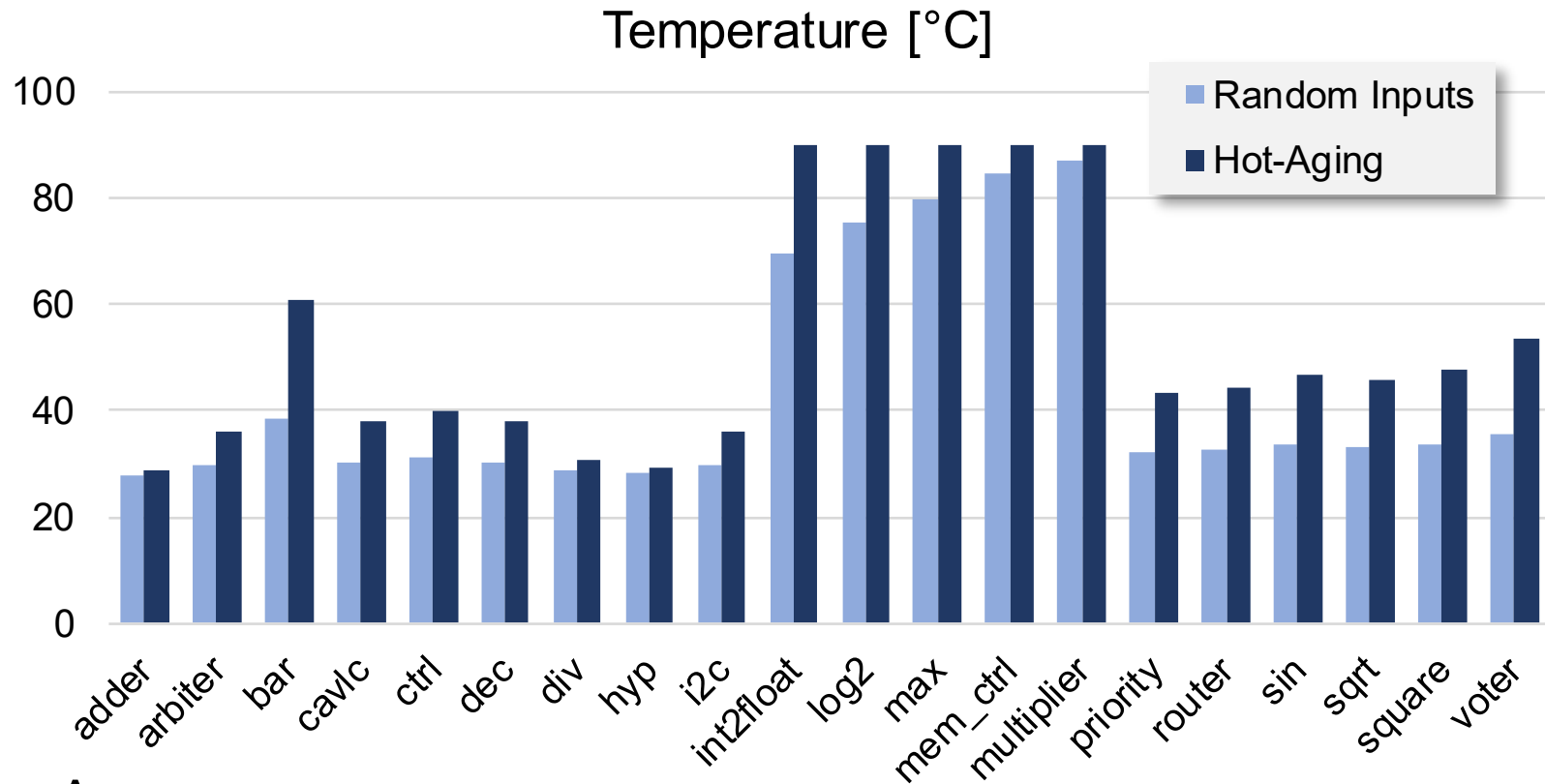
$$t_{age} = \delta \cdot \left(AF_{BTI}^{T_{op}, T_0} \right)^{-1} \left(\Delta t_{guard} \frac{\varepsilon \cdot t_{d,init}}{\Delta t_{d,T_0}} \right)^\varphi$$

- With:
 - $\delta, \varepsilon, \varphi$ – Extracted parameters for chosen technology

- 3 Analyses
 - Aging **without** and **with** consideration of **temperature**
 - Impact on **guard-banding**
- Input vectors
 - **Randomly generated** (modeling typical use case)
 - **Critical case (GA)** (can be malicious or unintentionally)
- Circuits from **EPFL benchmark suite**



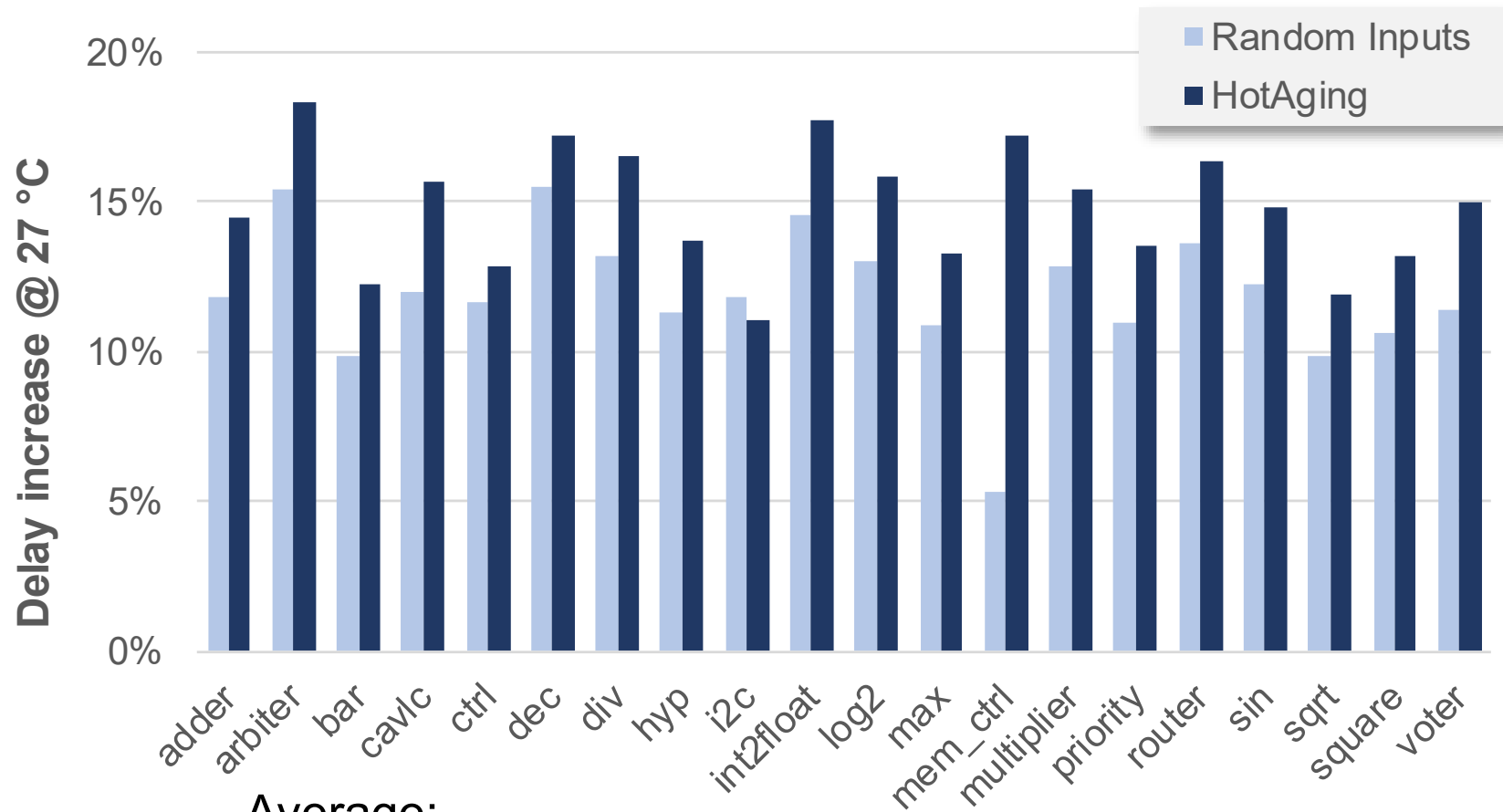
Results – Temp. increase



Average:

- Random inputs increase temperature by 16°C
- Hot-Aging increases temperature by 26°C

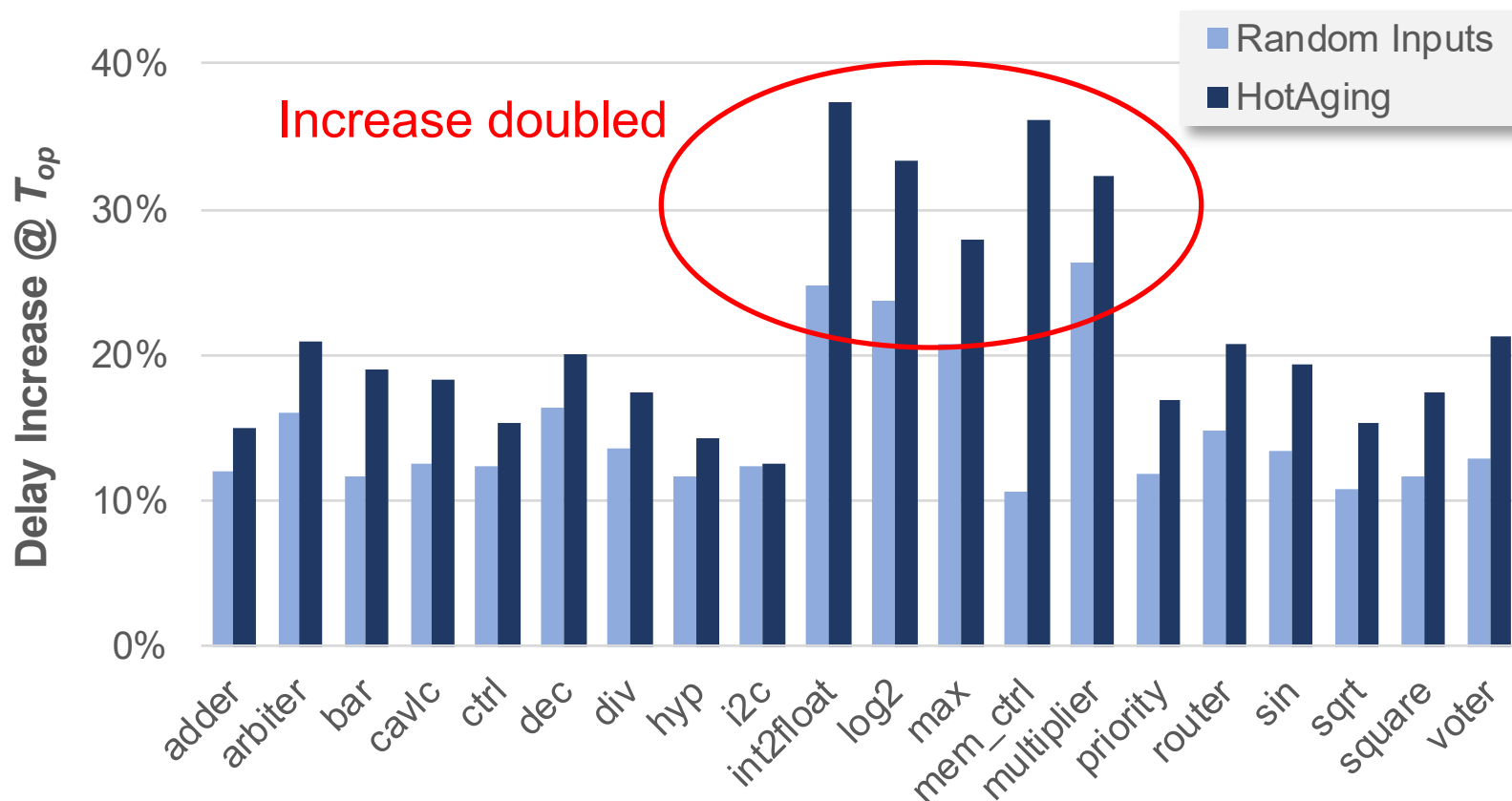
Results – Delay incr. @ 27°C (10y)



Average:

- Random inputs increase delay by 12%
- Hot-Aging increases delay by 15%

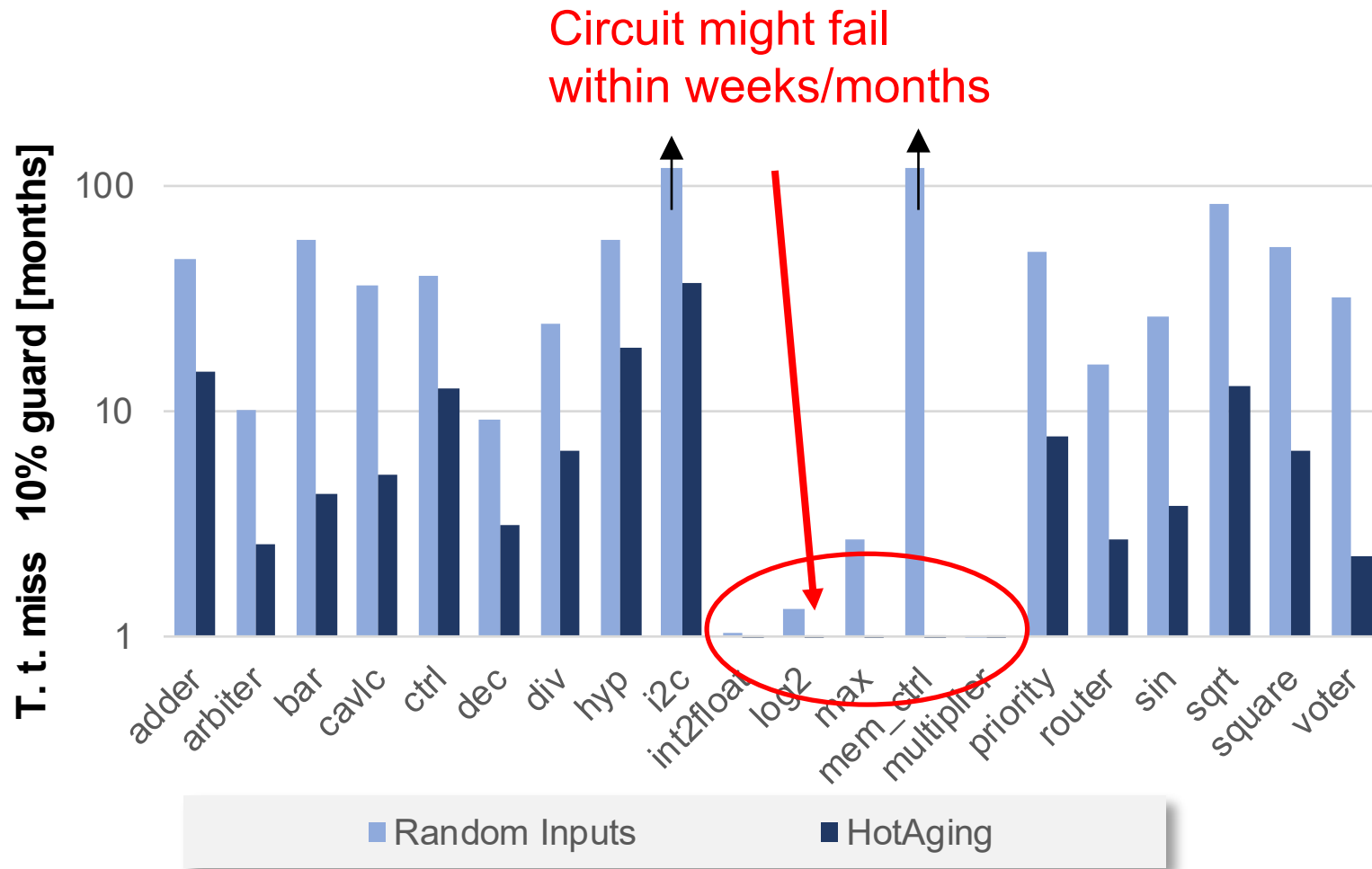
Results: Delay incr. @ T_{op} (10y)



Worst case:

- Random inputs increase delay by 26%
- Hot-Aging increases delay by 40%

Results: Time to miss 10% guard [months]





- Exploration of **relation** between hardware **degradation** and **temperature**
- **Analysis environment**
 - Extraction of random and worst case input scenarios
 - Determination of how aging and temperature impact the circuit delay.
- **Results** indicate
 - If temperature is considered: degradation can **increase** by more than **factor 2**
 - If **guard-banding** is applied: circuits can enter malfunction states within **months** (random case) or even within **weeks** (critical case).
- There is a **need for appropriate countermeasures**

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